precipitating at least one passivating material on at least a side wall of the laterally defined structure at least from time to time at least one of prior to the anisotropic plasma etching and during the anisotropic plasma etching;

adding at least one fluorine-delivering etching gas to the process gas at least from time to time, the at least one fluorine-delivering etching gas including at least one compound selected from the group of CIF₃, BrF₃ and IF₅;

adding NF₃ to the process gas at least from time to time as an additive for consuming the at least one passivating material; and

adding at least one of a light and easily ionizable gas, H₂, He, and Ne to the process gas at least from time to time.

- 35. (New) The method of claim 34, further comprising the step of adding at least one gas selected from the group of SiF₄, C_4F_8 , C_3F_6 , C_4F_{10} , C_3F_8 and C_2F_6 to the process gas at least from time to time as the gas forming the at least one passivating material.
- 36. (New) The method of claim 34, further comprising the step of adding at least one gas selected from the group of O₂, N₂O, NO, NO_x, CO₂, Ar, NO₂ and N₂ to the process gas at least from time to time.:--.

Remarks

This Preliminary Amendment cancels, without prejudice, original claims 1 to 18 in the underlying PCT Application No. PCT/DE00/00821, and adds new claims 19 to 36. The new claims conform the claims to U.S. Patent and Trademark Office rules and do not add new matter to the application.

The above amendments to the specification and abstract are to conform the specification and abstract to U.S. Patent and Trademark Office rules or to correct informalities, and do not introduce new matter into the application.

The underlying PCT Application No. PCT/DE00/00821 includes an International Search Report, dated September 26, 2000. The Search Report includes a list of documents that were uncovered in the underlying PCT Application. A copy of the Search Report accompanies this Preliminary Amendment.

Applicants assert that the subject matter of the present application is new, nonobvious, and useful. Prompt consideration and allowance of the application are respectfully requested.

Respectfully Submitted.

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